# organic compounds

Acta Crystallographica Section E Structure Reports Online

ISSN 1600-5368

# 1,3-Bis(chloromethyl)benzene

#### Marisa B. Sanders, David Leon, Eddy I. Ndichie and Benny C. Chan\*

Department of Chemistry, The College of New Jersey, 2000 Pennington Rd, Ewing, NJ 08628, USA

Correspondence e-mail: chan@tcnj.edu

Received 5 March 2013; accepted 12 June 2013

Key indicators: single-crystal X-ray study; T = 100 K; mean  $\sigma$ (C–C) = 0.002 Å; *R* factor = 0.023; *wR* factor = 0.064; data-to-parameter ratio = 21.4.

The title compound,  $C_8H_8Cl_2$ , used in the synthesis of many pharmaceutical intermediates, forms a three-dimensional network through chlorine–chlorine interactions in the solidstate that measure 3.513 (1) and 3.768 (3) Å.

#### **Related literature**

For background information on the applications of halogenated xylenes, see: Ito & Tada (2009); Zordan & Brammer (2006). For related structures, see: Castaner *et al.* (1991). For halogen–halogen interactions, see: Hathwar *et al.* (2010). For additional information on how the space group of the structure was solved, see Spek (2009).



#### Experimental

Crystal data  $C_8H_8Cl_2$  $M_r = 175.04$ 

Orthorhombic, *Pbca* a = 8.5174 (5) Å b = 12.3094 (7) Å c = 15.2597 (9) Å V = 1599.89 (16) Å<sup>3</sup> Z = 8

#### Data collection

Bruker APEXII CCD diffractometer Absorption correction: multi-scan (SADABS; Bruker, 2011)  $T_{min} = 0.665, T_{max} = 0.746$ 

Refinement

 $R[F^2 > 2\sigma(F^2)] = 0.023$  $wR(F^2) = 0.064$ S = 1.041949 reflections Mo K $\alpha$  radiation  $\mu = 0.73 \text{ mm}^{-1}$  T = 100 K $0.51 \times 0.50 \times 0.10 \text{ mm}$ 

17126 measured reflections 1949 independent reflections 1782 reflections with  $I > 2\sigma(I)$  $R_{int} = 0.026$ 

91 parameters H-atom parameters constrained  $\Delta \rho_{max} = 0.39 \text{ e} \text{ Å}^{-3}$  $\Delta \rho_{min} = -0.24 \text{ e} \text{ Å}^{-3}$ 

Data collection: *APEX2* (Bruker, 2011); cell refinement: *SAINT* (Bruker, 2011); data reduction: *SAINT*; program(s) used to solve structure: *SHELXS97* (Sheldrick, 2008); program(s) used to refine structure: *SHELXL97* (Sheldrick, 2008); molecular graphics: *CrystalMaker* (CrystalMaker Software, 2009); software used to prepare material for publication: *enCIFer* (Allen *et al.* 2004).

The authors gratefully acknowledge The College of New Jersey's School of Science for research funding and the National Science Foundation for major research instrumentation grant (NSF-0922931) for diffractometer acquisition.

Supplementary data and figures for this paper are available from the IUCr electronic archives (Reference: MW2106).

#### References

Allen, F. H., Johnson, O., Shields, G. P., Smith, B. R. & Towler, M. (2004). J. Appl. Cryst. 37, 335–338.

- Bruker (2011). APEX2, SAINT and SADABS. Bruker AXS Inc., Madison, Wisconsin, USA.
- Castaner, J., Riera, J., Carilla, J., Robert, A., Molins, E. & Miravitlles, C. (1991). J. Org. Chem. 56, 103-.
- CrystalMaker Software (2009). CrystalMaker for Windows. CrystalMaker Software Ltd, Oxford, England.

Hathwar, V., Roopan, S., Subashini, R., Khan, F. & Row, T. (2010). J. Chem. Sci. 122, 677–685.

Ito, A. & Tada, N. (2009). *Jpn Kokai Tokkyo Koho*, JP 2009242338 A 20091022 Sheldrick, G. M. (2008). *Acta Cryst.* A**64**, 112–122.

Spek, A. L. (2009). Acta Cryst. D65, 148-155.

Zordan, F. & Brammer, L. (2006). Cryst. Growth Des. 6, 1374–1379.

# supporting information

## Acta Cryst. (2013). E69, o1150 [https://doi.org/10.1107/S1600536813016383]

## 1,3-Bis(chloromethyl)benzene

## Marisa B. Sanders, David Leon, Eddy I. Ndichie and Benny C. Chan

#### S1. Comment

Halogenated xylenes, including the title compound, have a variety of applications in agrochemicals, drugs, and macromolecular materials (Ito and Tada, 2009). Most recently, these compounds have shown potential for their use in hard-coated film for optical devices (Ito and Tada, 2009). Compounds such as the title one that contain networks of halogen-halogen contacts also have a variety of applications in liquid crystals, topochemical reactions, conducting materials, and anion receptors (Zordan and Brammer, 2006). 1,3-Bis(chloromethyl)benzene is stabilized by chlorine-chlorine interactions of 3.513 (1) Å and 3.768 (3) Å. These contacts are within the normal range of chlorine-chlorine interactions, which are typically 3.546 Å to 3.813 Å (Hathwar *et al.*, 2010).

#### **S2. Experimental**

Approximately 100 mg of the title compound was dissolved in 2 ml of hexanes. The solution was evaporated slowly over one week to produce large, clear, block crystals.

#### **S3. Refinement**

The structure was solved using direct methods (Bruker, 2011).





Thermal ellipsoid plot at 50% probability.



#### Figure 2

The title structure is stabilized by chlorine-chlorine interactions that measure 3.513 (1) Å and 3.768 (3) Å to form a three dimensional network. Carbon atoms are shown in black, hydrogen atoms in pink, and chlorine atoms in green.

## 1,3-Bis(chloromethyl)benzene

### Crystal data

 $C_8H_8Cl_2$   $M_r = 175.04$ Orthorhombic, *Pbca*  a = 8.5174 (5) Å b = 12.3094 (7) Å c = 15.2597 (9) Å  $V = 1599.89 (16) Å^3$  Z = 8F(000) = 720

### Data collection

Bruker APEXII CCD	17126 measured reflections
diffractometer	1949 independent reflections
Radiation source: fine-focus sealed tube	1782 reflections with $I > 2\sigma(I)$
Graphite monochromator	$R_{\rm int} = 0.026$
Detector resolution: 8.3333 pixels mm <sup>-1</sup>	$\theta_{\rm max} = 28.6^\circ, \ \theta_{\rm min} = 2.7^\circ$
$\omega$ and $\varphi$ scans	$h = -11 \rightarrow 11$
Absorption correction: multi-scan	$k = -15 \rightarrow 15$
(SADABS; Bruker, 2011)	$l = -20 \longrightarrow 20$
$T_{\min} = 0.665, \ T_{\max} = 0.746$	
Refinement	
Refinement on $F^2$	Secondary atom site location: difference Fourier
Least-squares matrix: full	map
$R[F^2 > 2\sigma(F^2)] = 0.023$	Hydrogen site location: inferred from
$wR(F^2) = 0.064$	neighbouring sites
S = 1.04	H-atom parameters constrained

 $D_{\rm x} = 1.453 {\rm Mg} {\rm m}^{-3}$ 

 $\theta = 2.7 - 28.2^{\circ}$ 

 $\mu = 0.73 \text{ mm}^{-1}$ 

T = 100 K

 $D_{\rm m} = 1.453 \text{ Mg m}^{-3}$ 

Thick plate, colourless  $0.51 \times 0.50 \times 0.10$  mm

 $D_{\rm m}$  measured by not measured

Cell parameters from 120 reflections

Mo *K* $\alpha$  radiation,  $\lambda = 0.71073$  Å

1949 reflections $w = 1/[\sigma^2(F_o^2) + (0.0356P)^2 + 0.6168P]$ 91 parameterswhere  $P = (F_o^2 + 2F_c^2)/3$ 0 restraints $(\Delta/\sigma)_{max} = 0.001$ Primary atom site location: structure-invariant $\Delta \rho_{max} = 0.39$  e Å<sup>-3</sup> $\Delta \rho_{min} = -0.24$  e Å<sup>-3</sup>

### Special details

**Geometry**. All e.s.d.'s (except the e.s.d. in the dihedral angle between two l.s. planes) are estimated using the full covariance matrix. The cell e.s.d.'s are taken into account individually in the estimation of e.s.d.'s in distances, angles and torsion angles; correlations between e.s.d.'s in cell parameters are only used when they are defined by crystal symmetry. An approximate (isotropic) treatment of cell e.s.d.'s is used for estimating e.s.d.'s involving l.s. planes.

**Refinement**. Refinement of  $F^2$  against ALL reflections. The weighted *R*-factor *wR* and goodness of fit *S* are based on  $F^2$ , conventional *R*-factors *R* are based on *F*, with *F* set to zero for negative  $F^2$ . The threshold expression of  $F^2 > \sigma(F^2)$  is used only for calculating *R*-factors(gt) *etc.* and is not relevant to the choice of reflections for refinement. *R*-factors based on  $F^2$  are statistically about twice as large as those based on *F*, and *R*- factors based on ALL data will be even larger.

Fractional atomic coordinates an	d isotropic or equivale	nt isotropic displacement	parameters (Å	ĺ²)
----------------------------------	-------------------------	---------------------------	---------------	-----

				TT 4/TT	
	<i>x</i>	<u> </u>	Z	$U_{\rm iso} * / U_{\rm eq}$	
Cl1	0.61622 (3)	0.35365 (2)	1.030229 (18)	0.02078 (9)	
Cl2	0.83843 (3)	0.32450 (2)	0.660472 (18)	0.02164 (10)	
C1	0.81471 (14)	0.40672 (11)	1.02366 (8)	0.0210 (3)	
H1A	0.8343	0.4563	1.0736	0.025*	

# supporting information

111D	0.8000	0.2462	1.0272	0.025*
HIB	0.8909	0.3462	1.0272	0.025*
C2	0.83655 (13)	0.46689 (10)	0.93903 (7)	0.0159 (2)
C3	0.90389 (13)	0.41528 (9)	0.86690 (8)	0.0161 (2)
Н3	0.9394	0.3424	0.8722	0.019*
C4	0.91971 (13)	0.46956 (9)	0.78693 (7)	0.0165 (2)
C5	0.98635 (14)	0.41163 (11)	0.70880 (8)	0.0218 (3)
H5A	1.0779	0.3675	0.7269	0.026*
H5B	1.0224	0.4654	0.6650	0.026*
C6	0.78830 (13)	0.57490 (10)	0.93140 (8)	0.0182 (2)
H6	0.7434	0.6110	0.9804	0.022*
C7	0.80570 (15)	0.62972 (10)	0.85252 (8)	0.0209 (2)
H7	0.7736	0.7034	0.8478	0.025*
C8	0.87016 (14)	0.57693 (10)	0.78021 (8)	0.0196 (2)
H8	0.8803	0.6144	0.7261	0.024*

Atomic displacement parameters  $(Å^2)$ 

	$U^{11}$	<i>U</i> <sup>22</sup>	<i>U</i> <sup>33</sup>	$U^{12}$	$U^{13}$	U <sup>23</sup>
Cl1	0.01567 (15)	0.02646 (17)	0.02020 (16)	-0.00530 (11)	0.00008 (10)	0.00373 (11)
Cl2	0.02070 (16)	0.02609 (17)	0.01814 (15)	-0.00366 (11)	0.00164 (10)	-0.00641 (11)
C1	0.0148 (5)	0.0300 (7)	0.0181 (6)	-0.0067 (5)	-0.0028 (4)	0.0046 (5)
C2	0.0113 (5)	0.0219 (6)	0.0145 (5)	-0.0039 (4)	-0.0025 (4)	0.0009 (4)
C3	0.0121 (5)	0.0165 (5)	0.0196 (6)	-0.0015 (4)	-0.0019 (4)	0.0000 (4)
C4	0.0117 (5)	0.0216 (6)	0.0162 (5)	-0.0028 (4)	-0.0004(4)	-0.0022 (4)
C5	0.0150 (5)	0.0298 (7)	0.0206 (6)	-0.0035 (5)	0.0013 (4)	-0.0065 (5)
C6	0.0158 (5)	0.0216 (6)	0.0173 (5)	-0.0008 (4)	0.0018 (4)	-0.0041 (4)
C7	0.0209 (6)	0.0166 (6)	0.0250 (6)	0.0013 (4)	0.0000 (5)	0.0012 (5)
C8	0.0192 (5)	0.0227 (6)	0.0171 (5)	-0.0017 (5)	0.0000 (4)	0.0039 (5)

Geometric parameters (Å, °)

Cl1—C1	1.8152 (12)	C4—C8	1.3912 (17)
Cl2—C5	1.8115 (12)	C4—C5	1.5007 (16)
C1—C2	1.5004 (16)	С5—Н5А	0.9900
C1—H1A	0.9900	С5—Н5В	0.9900
C1—H1B	0.9900	C6—C7	1.3879 (17)
C2—C3	1.3944 (16)	С6—Н6	0.9500
C2—C6	1.3964 (17)	С7—С8	1.3933 (17)
C3—C4	1.3978 (16)	С7—Н7	0.9500
С3—Н3	0.9500	C8—H8	0.9500
C2—C1—Cl1	109.92 (8)	C4—C5—Cl2	109.97 (8)
C2—C1—H1A	109.7	C4—C5—H5A	109.7
Cl1—C1—H1A	109.7	Cl2—C5—H5A	109.7
C2C1H1B	109.7	C4—C5—H5B	109.7
Cl1—C1—H1B	109.7	Cl2—C5—H5B	109.7
H1A—C1—H1B	108.2	H5A—C5—H5B	108.2
C3—C2—C6	119.28 (11)	C7—C6—C2	120.25 (11)

# supporting information

C3—C2—C1	120.37 (11)	С7—С6—Н6	119.9	
C6—C2—C1	120.35 (11)	С2—С6—Н6	119.9	
C2—C3—C4	120.73 (11)	C6—C7—C8	120.14 (11)	
С2—С3—Н3	119.6	С6—С7—Н7	119.9	
С4—С3—Н3	119.6	С8—С7—Н7	119.9	
C8—C4—C3	119.29 (11)	C4—C8—C7	120.28 (11)	
C8—C4—C5	120.50 (11)	C4—C8—H8	119.9	
C3—C4—C5	120.19 (11)	С7—С8—Н8	119.9	